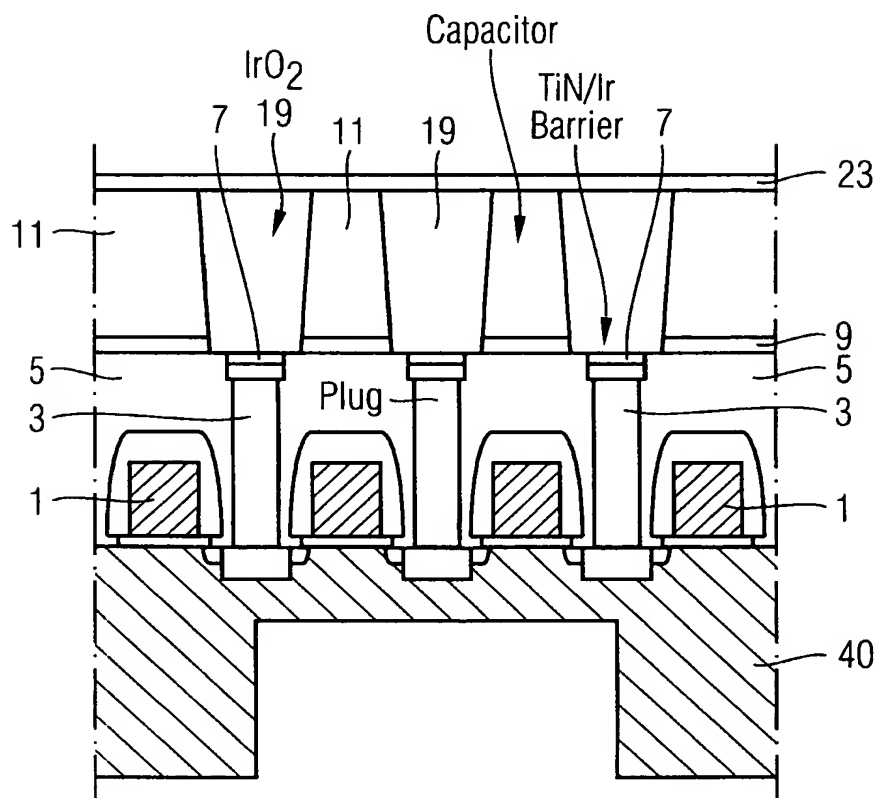




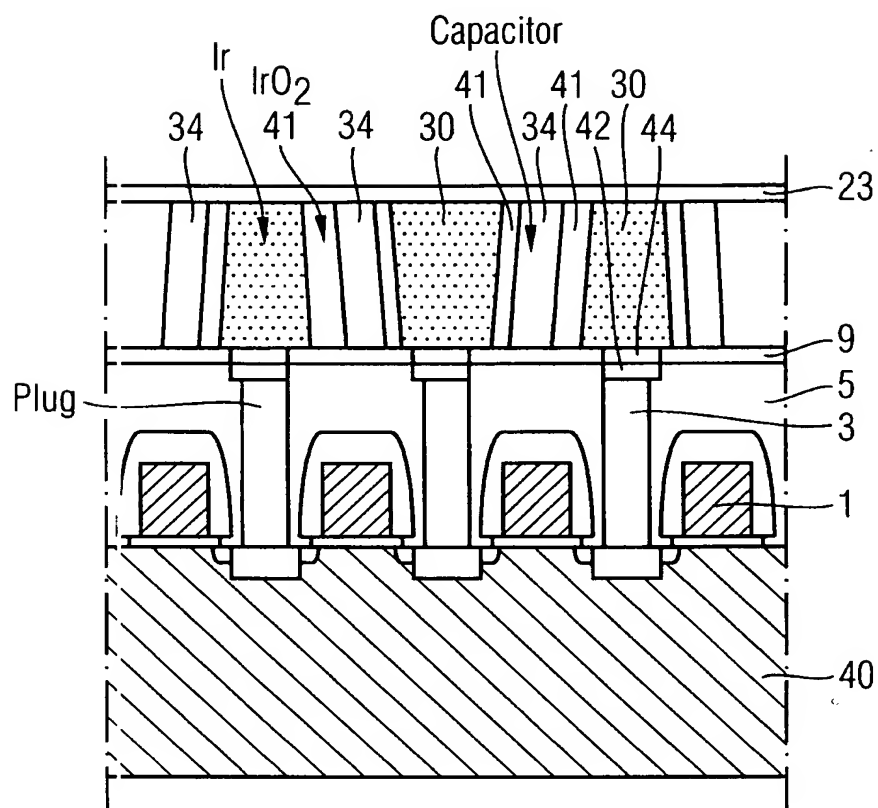
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FIG 1
Prior Art



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FIG 2

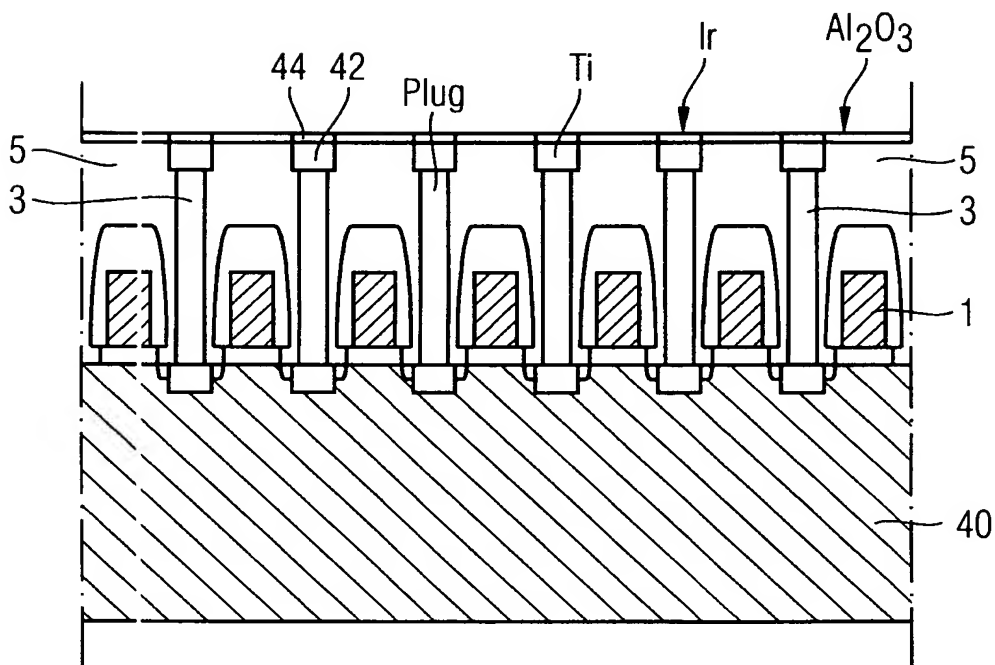




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FIG 3

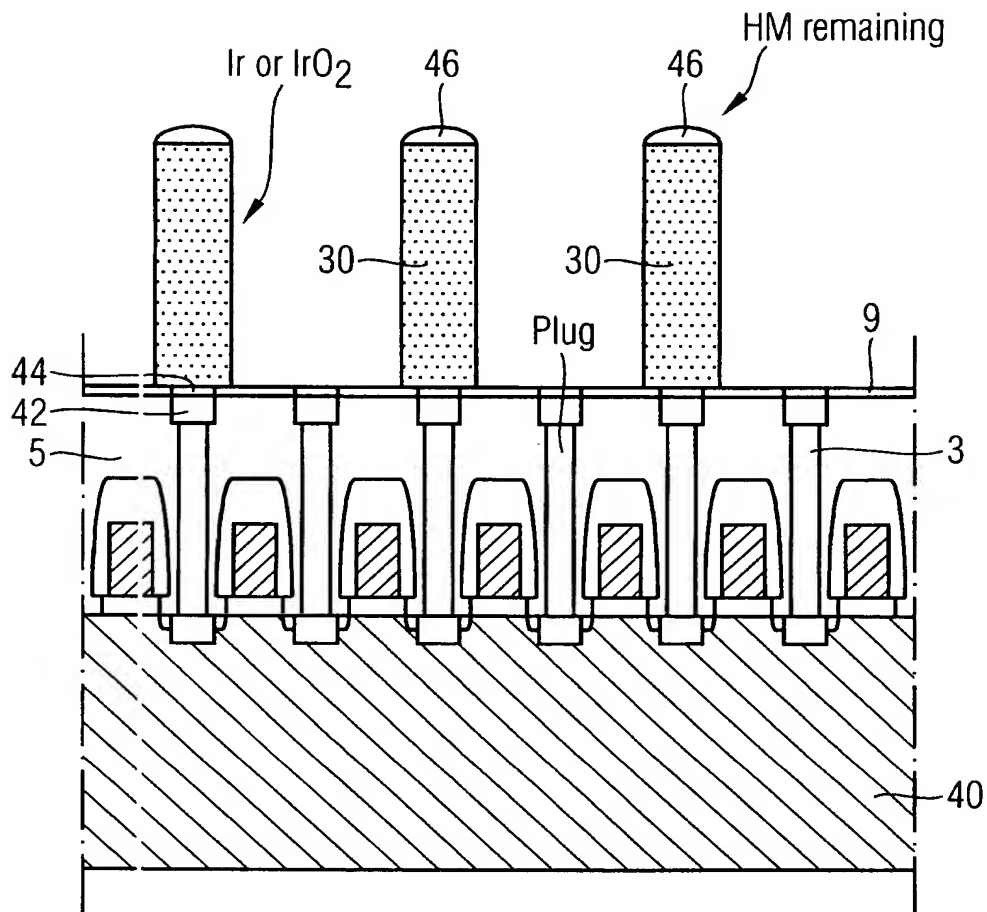
Before Capacitor Process



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FIG 4

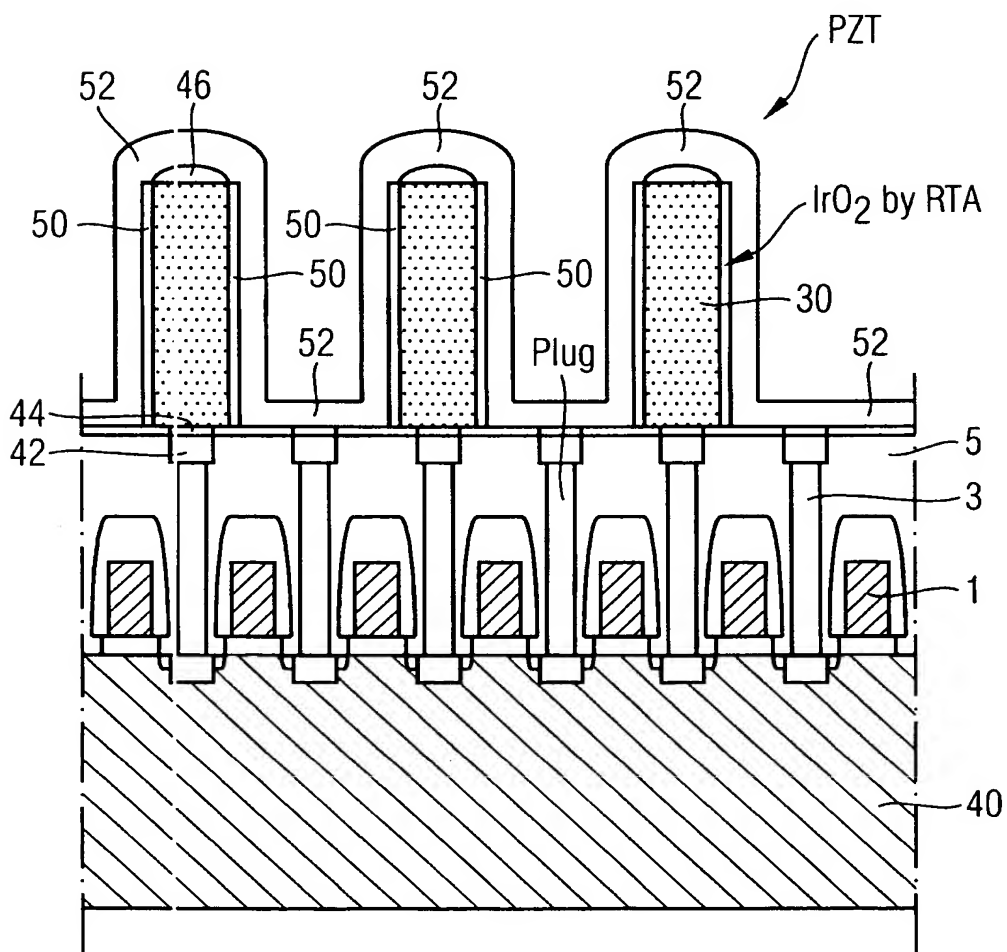
Ir or IrO₂ Deposit and RIE



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FIG 5

Making IrO₂ on Ir surface
(by RTA, if electrode is IrO₂, RTA is not necessary)
and PZT Deposit on Surface

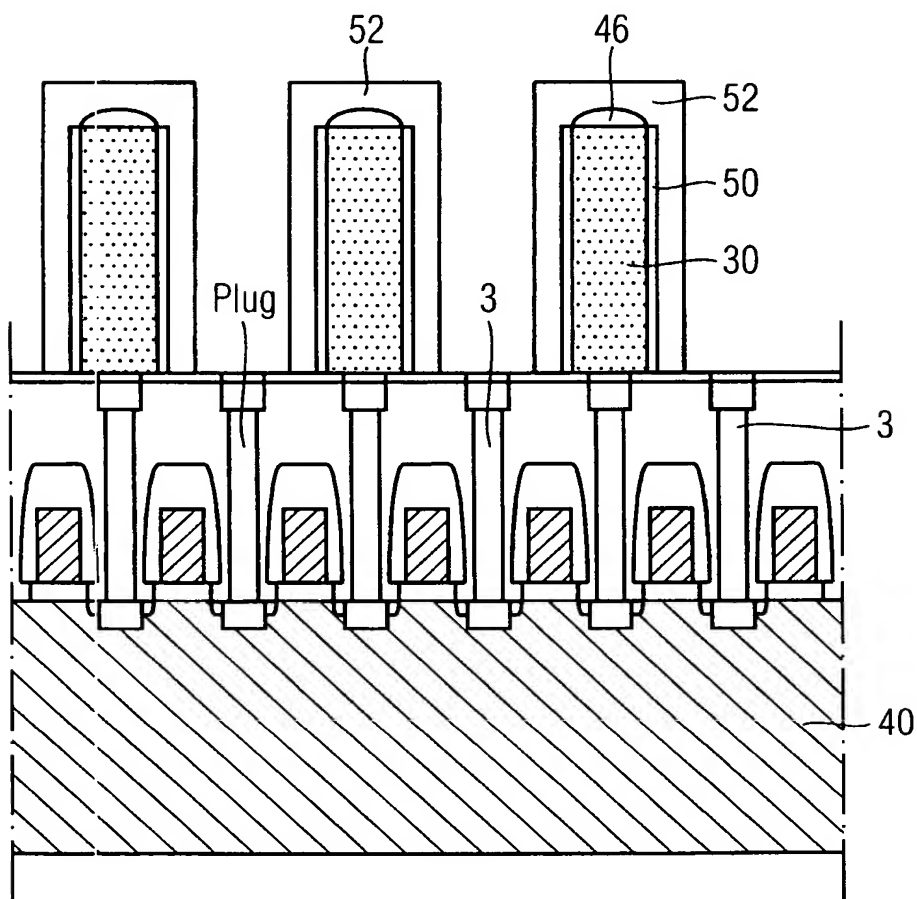




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FIG 6

PZT Etch Back



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FIG 7

Fill IrO_2 and Fill Ir
(Or Only fill IrO_2)
CMP and then Al_2O_3 deposit

